



IFW
PATENT
8007-1118

IN THE U.S. PATENT AND TRADEMARK OFFICE

In re application of

Masaru HOSOKAWA et al.

Conf. unknown

Application No. 10/594,567

Group unknown

Filed September 27, 2006

Examiner unknown

MATERIAL FOR CHEMICAL VAPOR DEPOSITION
AND THIN FILM FORMING METHOD

PRELIMINARY AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

November 1, 2006

Sir:

Prior to the first Official Action on the merits,
please amend the above-identified application as follows:

Amendments to the Specification begin on page 2 of this
paper.

Remarks begin on page 3 of this paper.